

Spin-dependent Tunneling Characteristics of Co₂MnSi-based Magnetic Tunnel Junctions with Co₅₀Fe₅₀ Insertion Layers

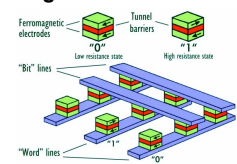
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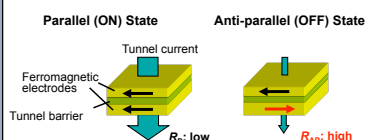
Introduction

Magnetoresistive Random Access Memory (MRAM)



- Non-volatile
- High speed
- High density
- Unlimited read/write endurance
- Principal switching component: magnetic tunnel junctions

Magnetic Tunnel Junctions (MTJs)



Key device parameter:

$$\text{TMR ratio} = \frac{R_{\text{ap}} - R_p}{R_p}$$

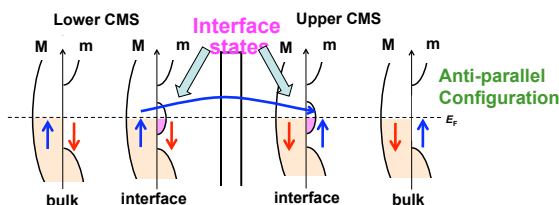
High spin-polarization is desirable to yield high TMR ratios

Heusler Alloy Half-Metallic Electrodes

- Complete spin polarization: only electrons of one spin involved in conduction
- Co₂MnSi (CMS) is a good candidate due to large energy gap for minority-spin electrons and high Curie temperature

Purpose

- Previously demonstrated CMS/MgO/CMS MTJs with TMR ratios up to **236% at RT and 1135% at 4.2K** (Ishikawa et al., Appl. Phys. Lett. 2009)
- Large drop in TMR ratio at high T might be due to MgO/CMS in-gap interface states combined with magnon excitations



Purpose of this study is to understand this phenomenon in order to fabricate devices with higher TMR ratios

Methods

Approach

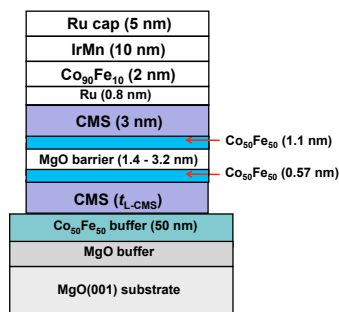
- Fabricate CMS-based MTJs with **interfacial insertion layers** in order to mitigate interfacial effects that tend to decrease TMR
- Measure and analyze the spin-dependent tunneling characteristics of these devices to elucidate tunneling paths

MTJ Fabrication

- MTJ layer structures were epitaxially grown on an MgO(001) substrate in a high vacuum chamber

- Layers deposited with magnetron sputtering and electron beam evaporation

- Samples processed using photolithography and argon ion milling



Results

TMR Characteristics

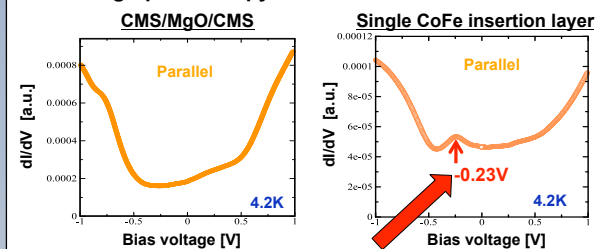
Layer structure	TMR Ratio	
	RT	4.2 K
MgO buff/CMS/MgO/CMS	236%	1135%
MgO buff/CoFe/MgO/CoFe	250%	350%
MgO buff/CoFe/MgO/CoFe/CMS	450%	1135%
MgO buff/CoFe buff/CMS/CoFe/MgO/CoFe/CMS	413%	1523%

- Presence of CMS dramatically improves TMR, indicating half-metallic characteristics
- Moreover, addition of insertion layers in CMS/MgO/CMS structures show further enhanced TMR

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Results (cont.)

Tunneling Spectroscopy

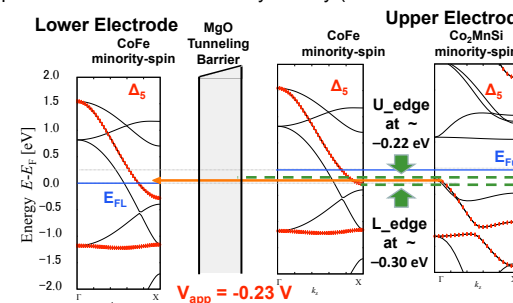


Peak at -0.23 V observed only in insertion layer MTJs

Discussion and Conclusion

Discussion

- Unique peak can be attributed to minority-to-minority tunneling path associated with the Δ_5 symmetry (-0.22 eV to -0.30 eV)



- Low inter-diffusion between CoFe and CMS: electrons supplied by CMS, and tunnel to lower electrode through CoFe
- Suggests that CoFe's primary role is to weaken magnon effects

Conclusion

- Demonstrated high TMR ratios up to 450% for CMS-based MTJs with Co₅₀Fe₅₀ insertion layers
- Tunneling spectroscopy confirmed that CMS acted as half-metallic spin-source while Co₅₀Fe₅₀ weakened magnon excitations
- Future work:
 - Understanding drop in TMR in double insertion layer MTJs
 - Further optimizing interfaces to enhance TMR